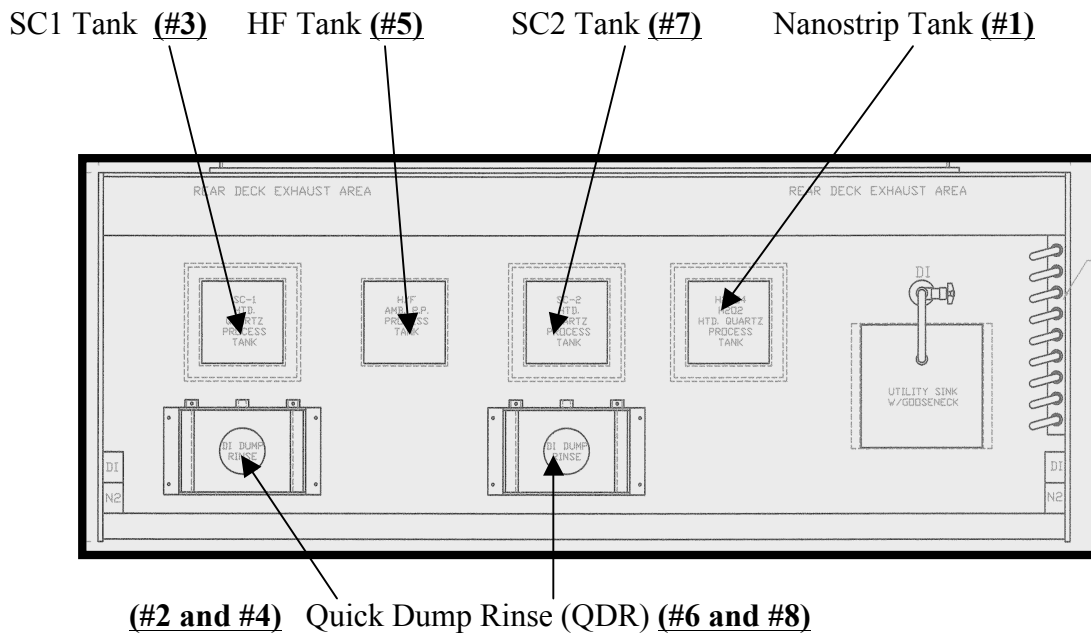


RCA Clean Bench

Notes:

- SC means standard clean.
- Do not use Piranha etch. We use Nanostrip instead (at RT).
- Local recovery of wastes as needed. QDRs dump to sanitary drain.
- Regular glassware, polypropylene or Teflon in everything but HF tank.
- Only Teflon or polypropylene in HF tank.
- Observe safety guidelines...hazardous chemicals involved in each step.



RCA Clean procedure for Silicon

Put wafers in carrier as needed

1. Nanostrip clean at RT for 5 minutes (*general cleaning*)
2. QDR for 5 minutes
3. SC1 (5:1:1 H₂O:NH₄OH:H₂O₂) for 10 minutes at 75 deg C (*particle removal*)
4. QDR for 5 minutes
5. HF (50:1 H₂O:HF) for 1 minute (*oxide removal*)
6. QDR for 5 minutes
7. SC2 (6:1:1 H₂O:HCl:H₂O₂) for 10 minutes at 75 deg C (*metals removal*)
8. QDR for 5 minutes

Spin Rinse Dry